

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	Docket Number (Optional) TWI-30261	Application Number NEW 10/621218
	Applicant(s) Kenneth Johnson et al.	
	Filing Date HEREWITH	Group Art Unit Unknown 2813

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
CAJ	*AA	4,053,232	10/11/1977	Dill et al.	250	225	04/28/1975
CAJ	*AB	4,757,207	07/12/1988	Chappelow et al.	250	491.1	03/03/1987
CAJ	*AC	4,999,014	03/12/1991	Gold et al.	356	369	05/04/1989
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FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

CAJ	*AK	W. Kong et al., "A Hybrid Analysis of Ellipsometry Data from Patterned Structures," <i>American Institute of Physics</i> , 1-56396-967-X/01, Characterization and Metrology for ULSI Technology: 2000 International Conference, 2001, pp. 373-377.
CAJ	*AL	M.E. Lee et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," International Conference on Characterization and Metrology for ULSI Technology, Gaithersburg, MD, March 23-27, 1998, <i>AIP Conference Proceedings</i> 449, pp. 331-5, 1998, pp. 1-5.
CAJ	*AM	W. Kong et al., "Analysis of Time-Evolved Spectroscopic Ellipsometry Data from Patterned Structures for Etching Process Monitoring and Control," paper 19.2, SRC TECHCON, Las Vegas, Nevada, September 9-11, 1998, 4 pages in length.
CAJ	*AN	P.A. Heimann, "Optical Etch-Rate Monitoring Using Active Device Areas: Lateral Interference Effects," <i>J. Electrochem. Soc.</i> , Vol. 132, No. 8, August 1985, pp. 2003-2006.
CAJ	*AO	P.A. Heimann et al., "Optical Etch-Rate Monitoring: Computer Simulation of Reflectance," <i>J. Electrochem. Soc.</i> , Vol. 131, No. 4, April 1984, pp. 881-885.
CAJ	*AP	H.L. Maynard et al., "Multiwavelength ellipsometry for real-time process control of the plasma etching of patterned samples," <i>J. Vac. Sci. Technol. B</i> , Vol. 15, No. 1, Jan/Feb 1997, pp. 109-115.

Examiner Craig A. Johnson	Date Considered 5/26/04
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	